

RF POWER DELIVERY FOR PLASMA PROCESSING USING MODULATED POWER SIGNAL

ABSTRACT OF THE DISCLOSURE

5 A plasma processing apparatus and a method of operating a plasma processing
apparatus are disclosed. In one embodiment, a first RF signal at a carrier frequency and a
second RF signal at a second frequency are generated. An amplitude modulated signal is
formed by modulating the first RF signal with the second RF signal. A plasma is generated
within the plasma processing chamber using the amplitude modulated signal. Generating
10 plasma using a frequency modulated signal is also disclosed.

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